

Special Topics on Basic EECS I Design Technology Co-Optimization

Lecture 13

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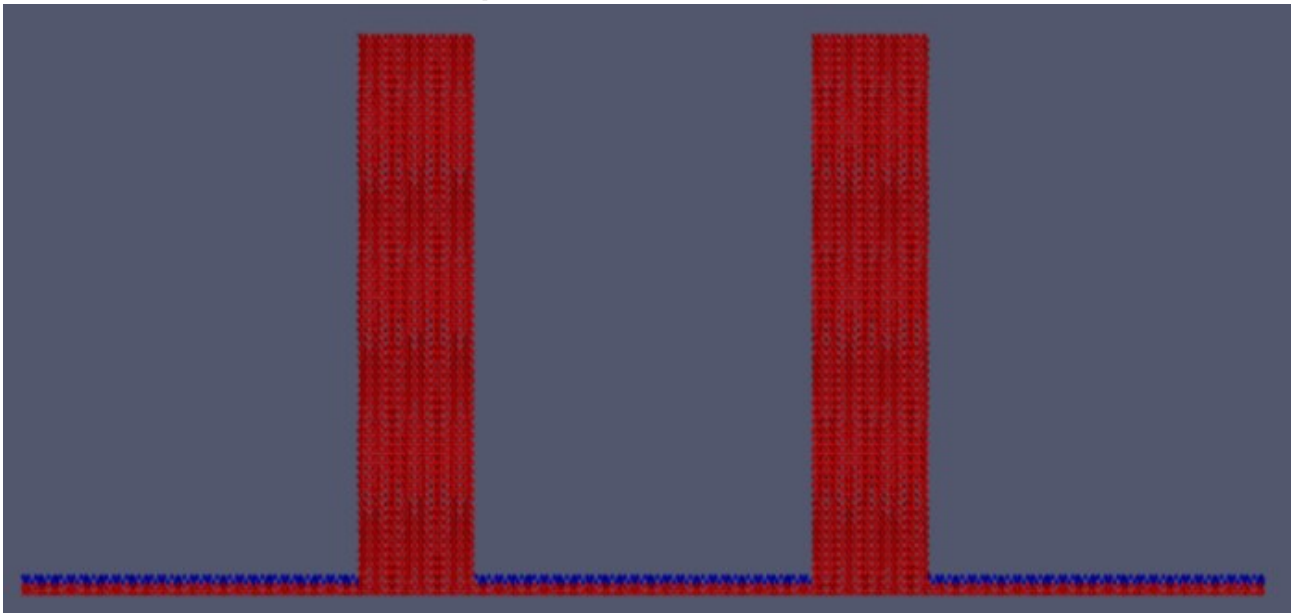
Department of Electrical Engineering and Computer Science

Gwangju Institute of Science and Technology (GIST)

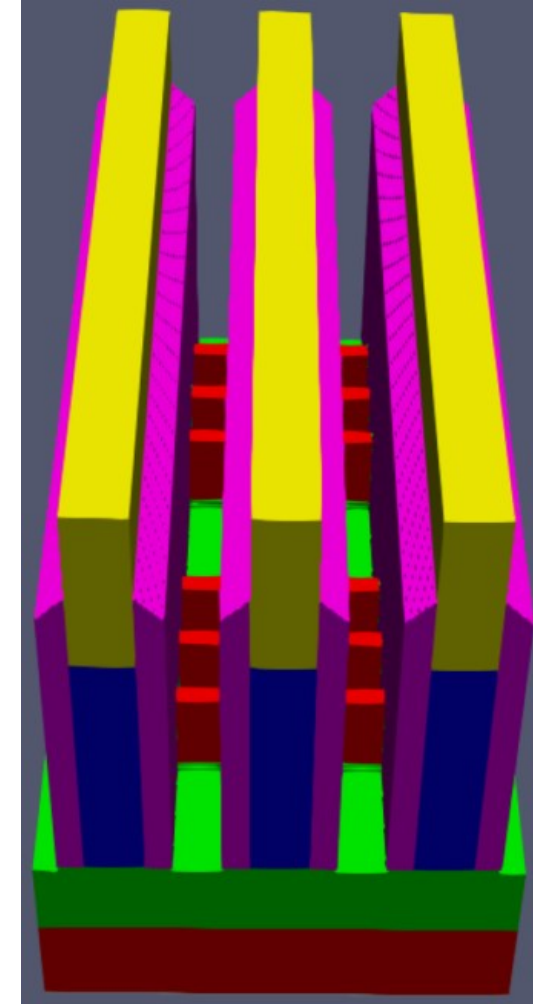
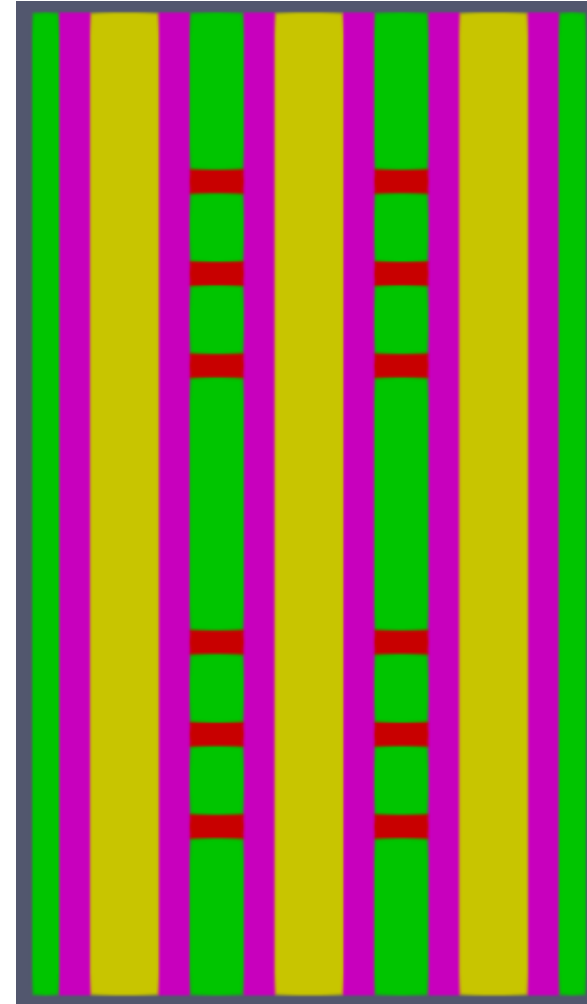
L13

Coming back to the FinFET

- There are fins.
 - Separated by 20 nm
 - Test a two-fin structure. (32-nm-tall)

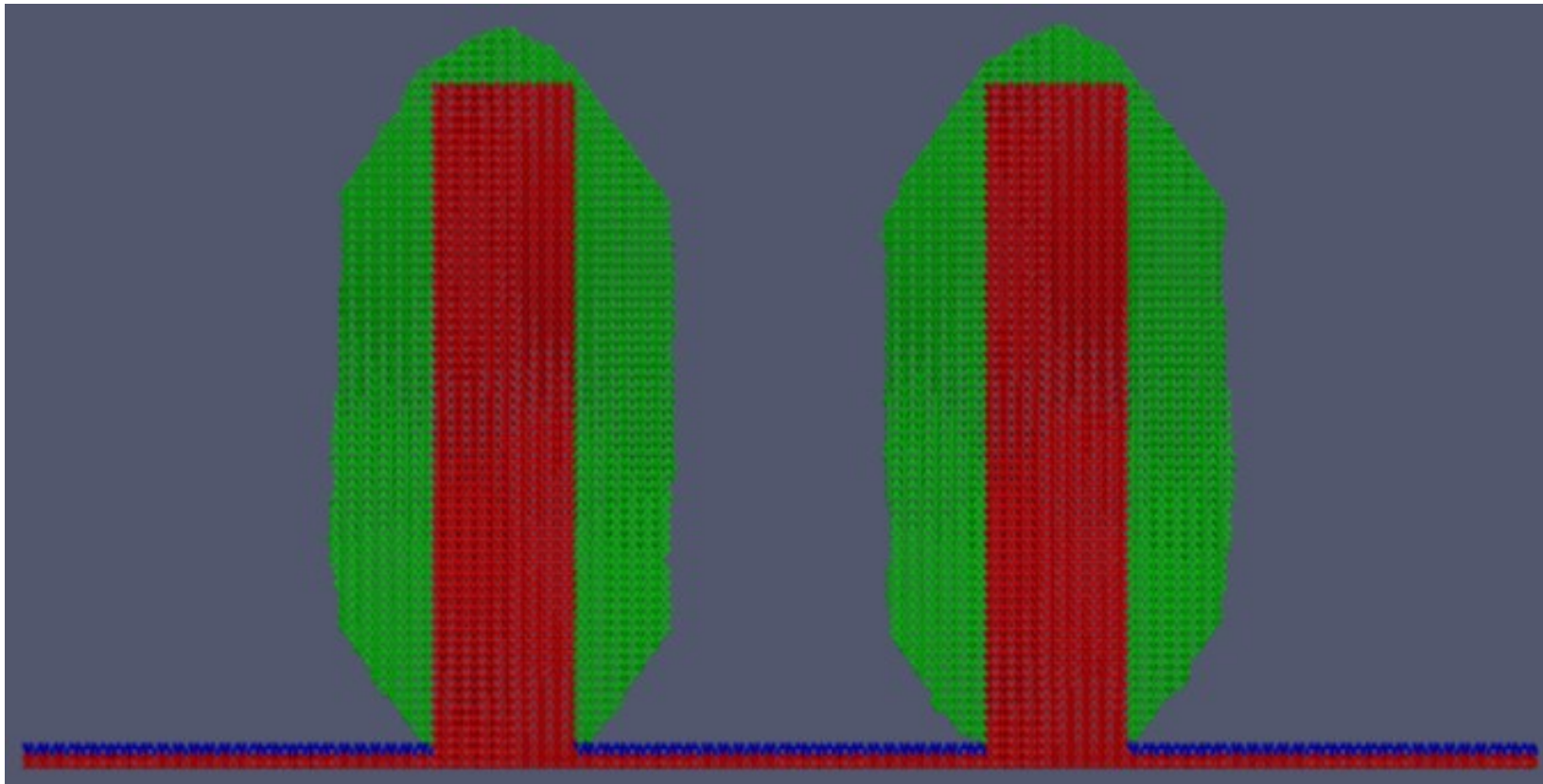


20 nm



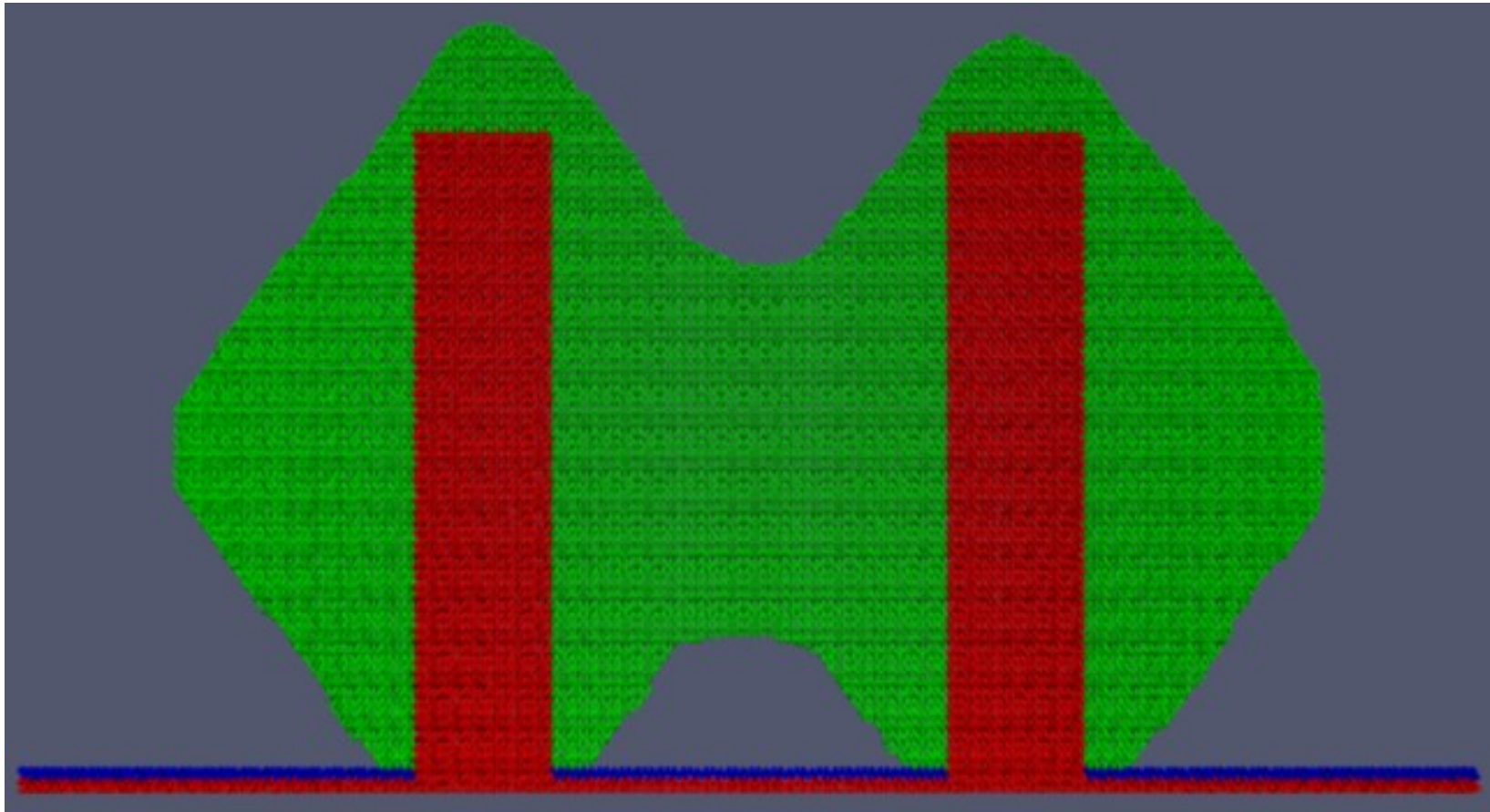
Thickness ~ 4.5 nm

- They are separated.
 - $\{111\}$ surfaces are observed.
 - On the top surface, $\{311\}$ surfaces are dominant.



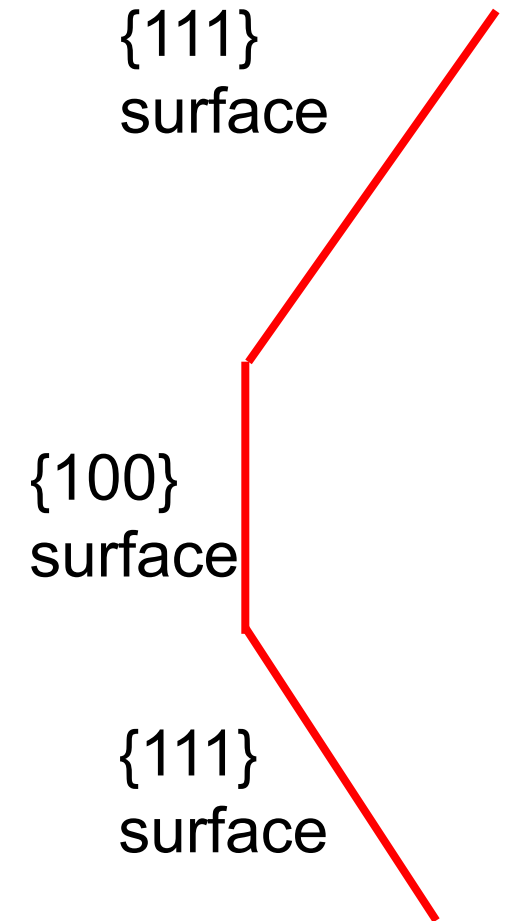
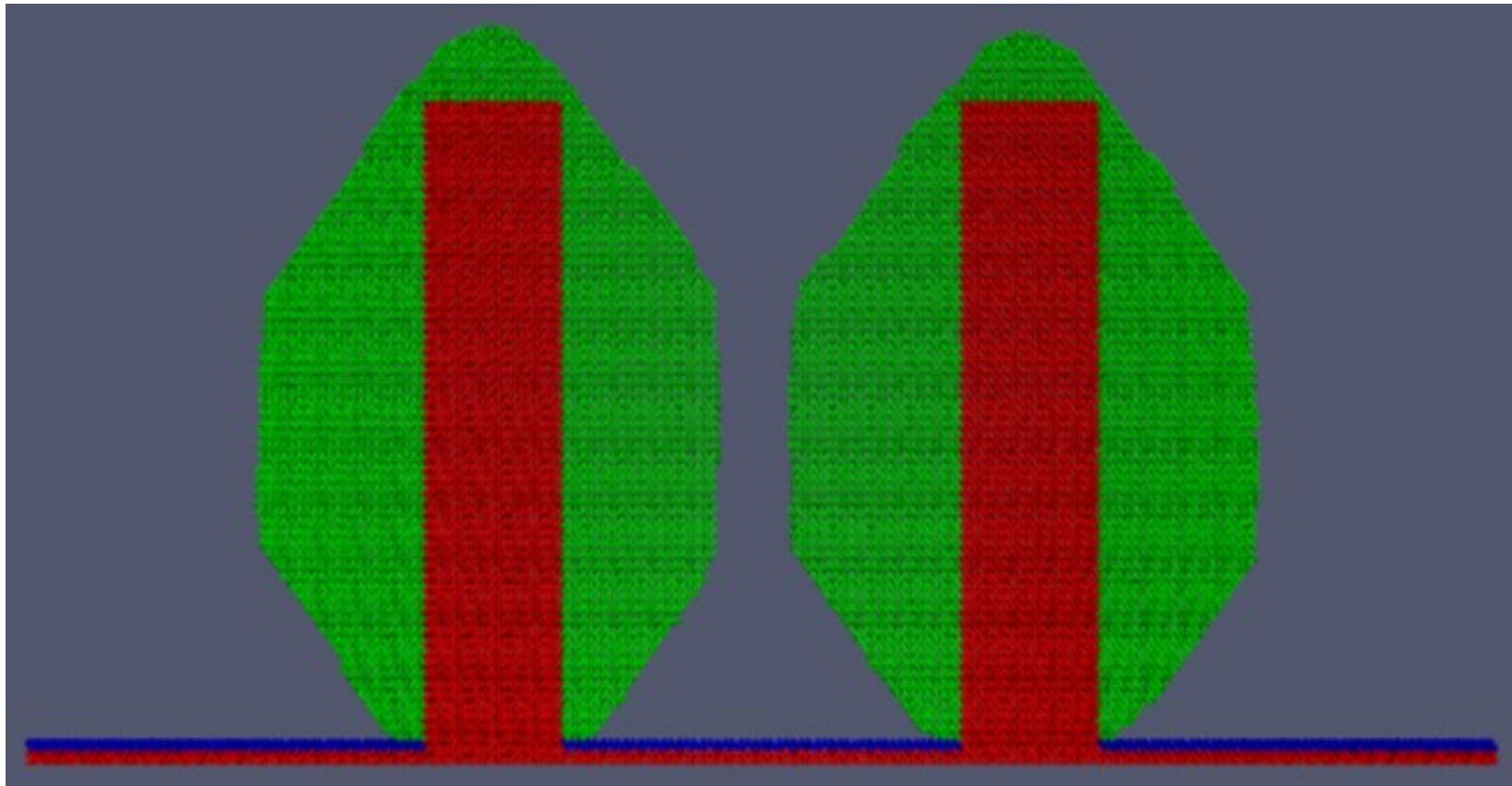
Double the number of atoms.

- They are bridged. It looks like mushrooms.
 - (Can we trust this result?)



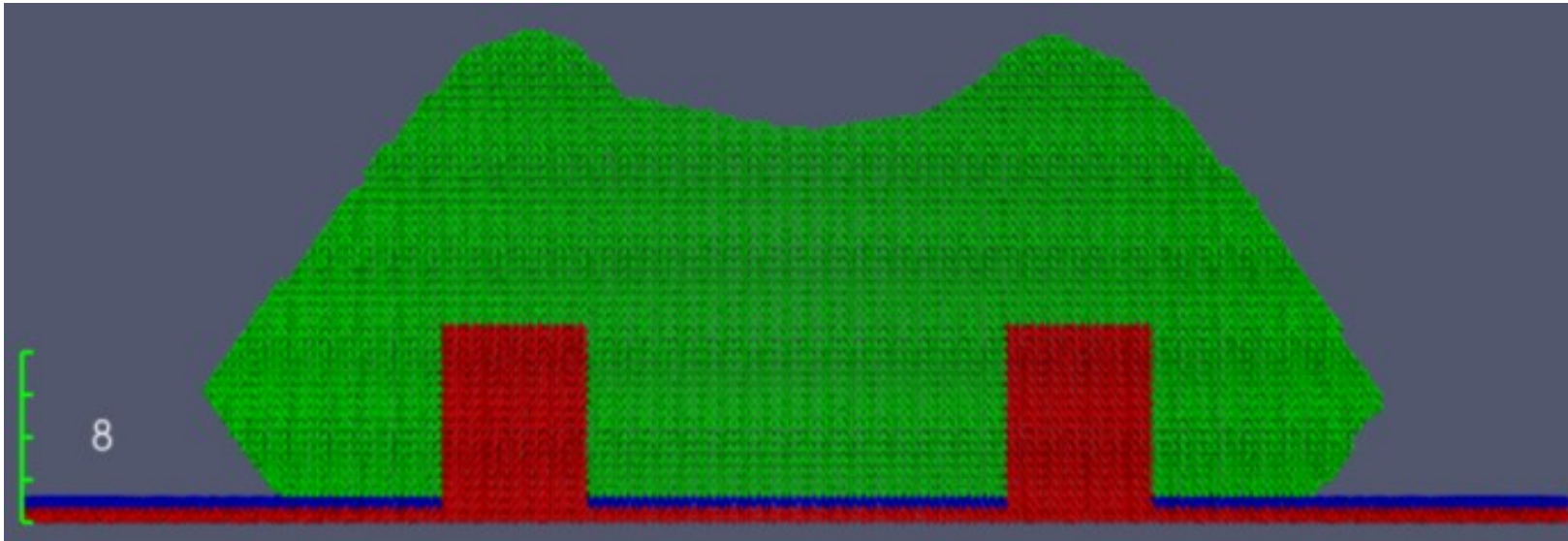
In between,

- We can find a condition of unmerged fins.
 - The fin shape can be well approximated.



Impact of fin height

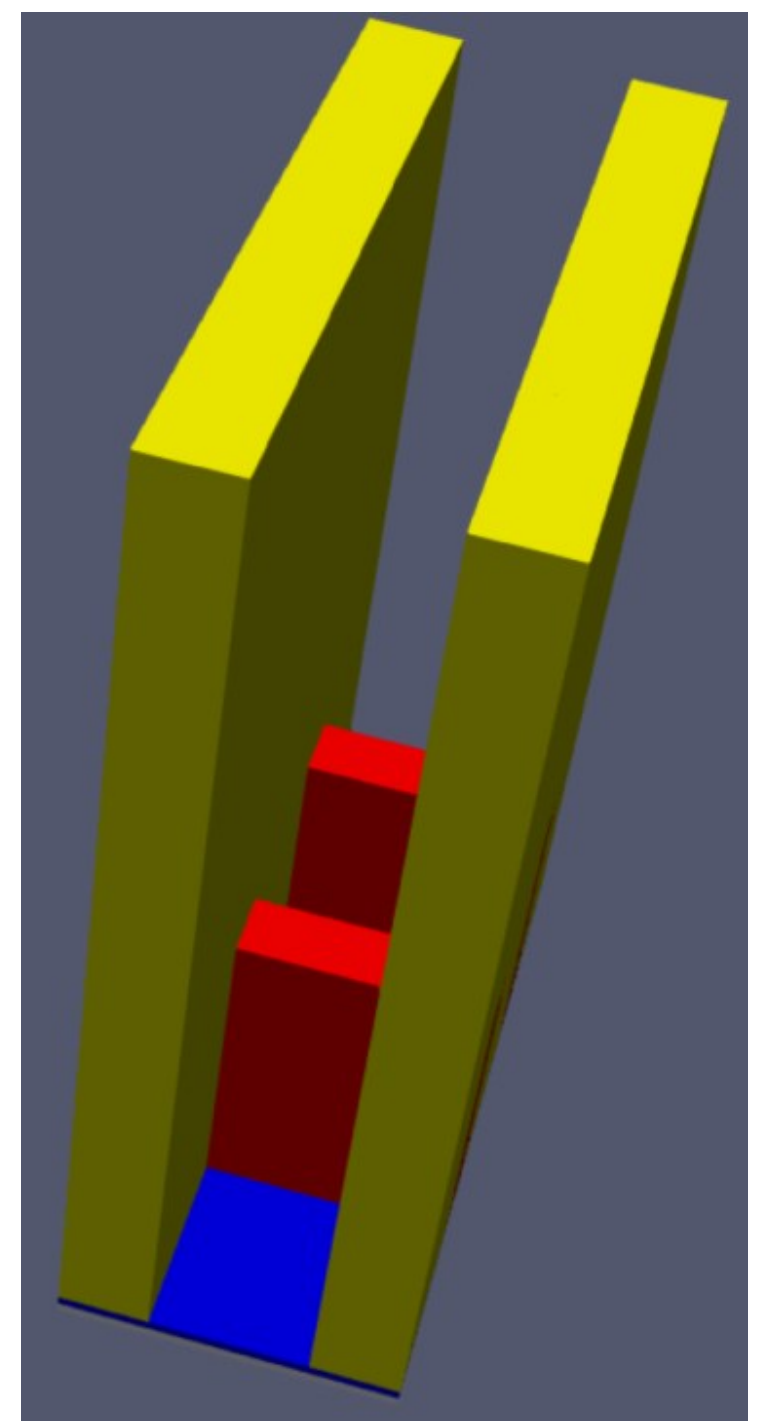
- Consider 8-nm-tall fins.
 - Repeat the previous test. (The same number of atoms in the last slide)



Try this.

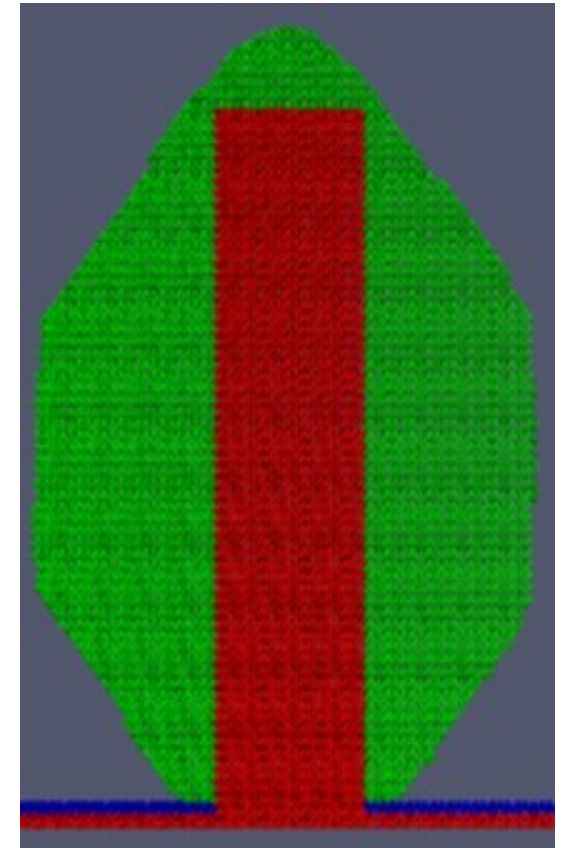
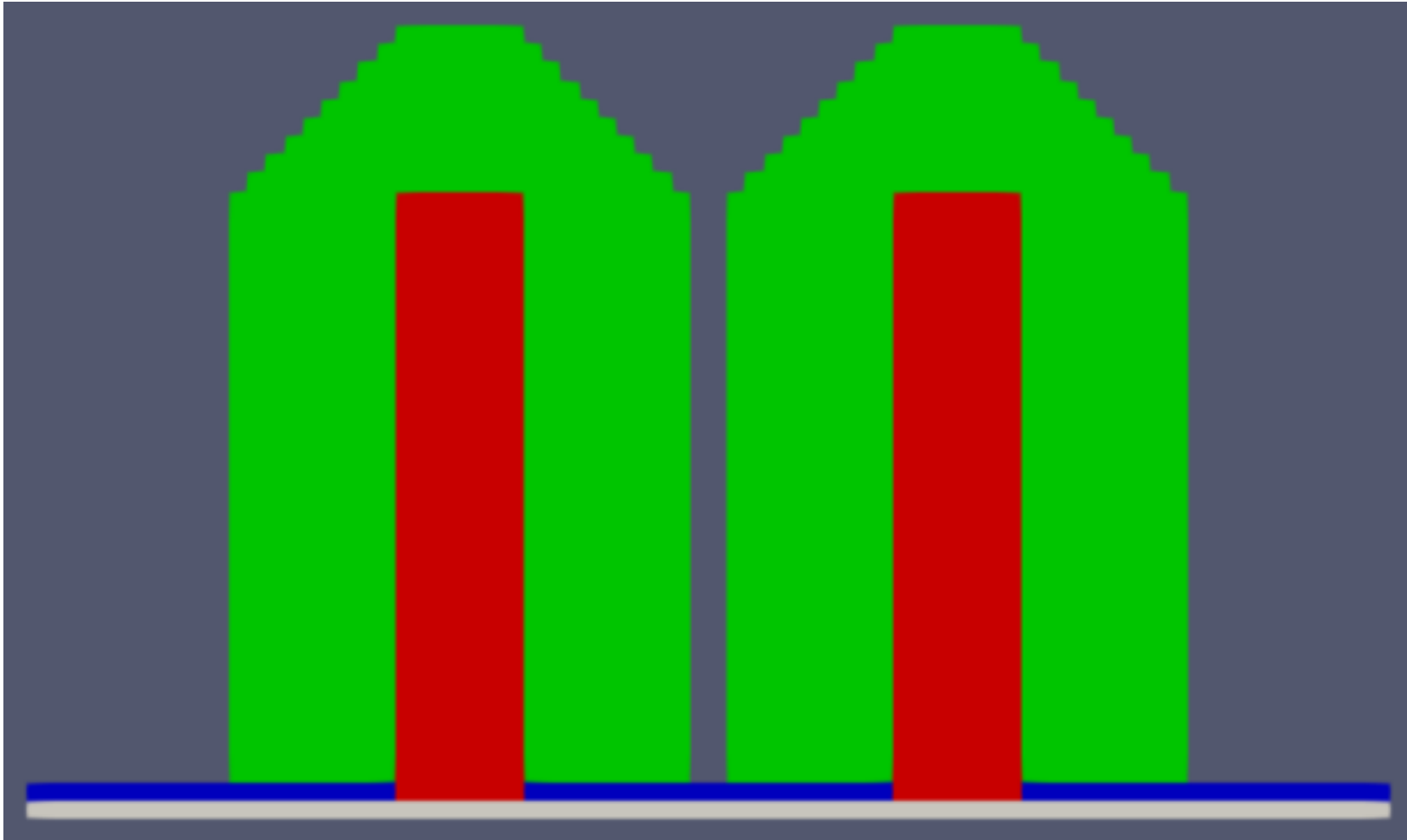
- Construct a test structure.
 - 34 nm (= 9 + 16 + 9) by 74 nm (= 20 + 7 + 20 + 7 + 20)
 - (The colors of the regions do not matter.)
 - Now, we are ready to test the selective epitaxial growth.

```
model (name="model_sd") {  
    select (region="Fin")  
    select (region="SD")  
}
```



Isotropic depo with a thickness of 9 nm

- No boundary condition. 45 degree.



New growth statement

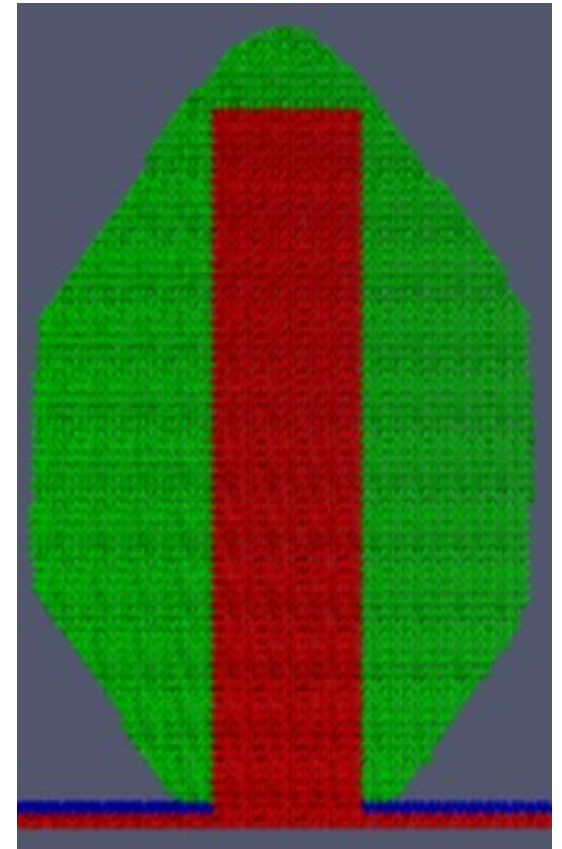
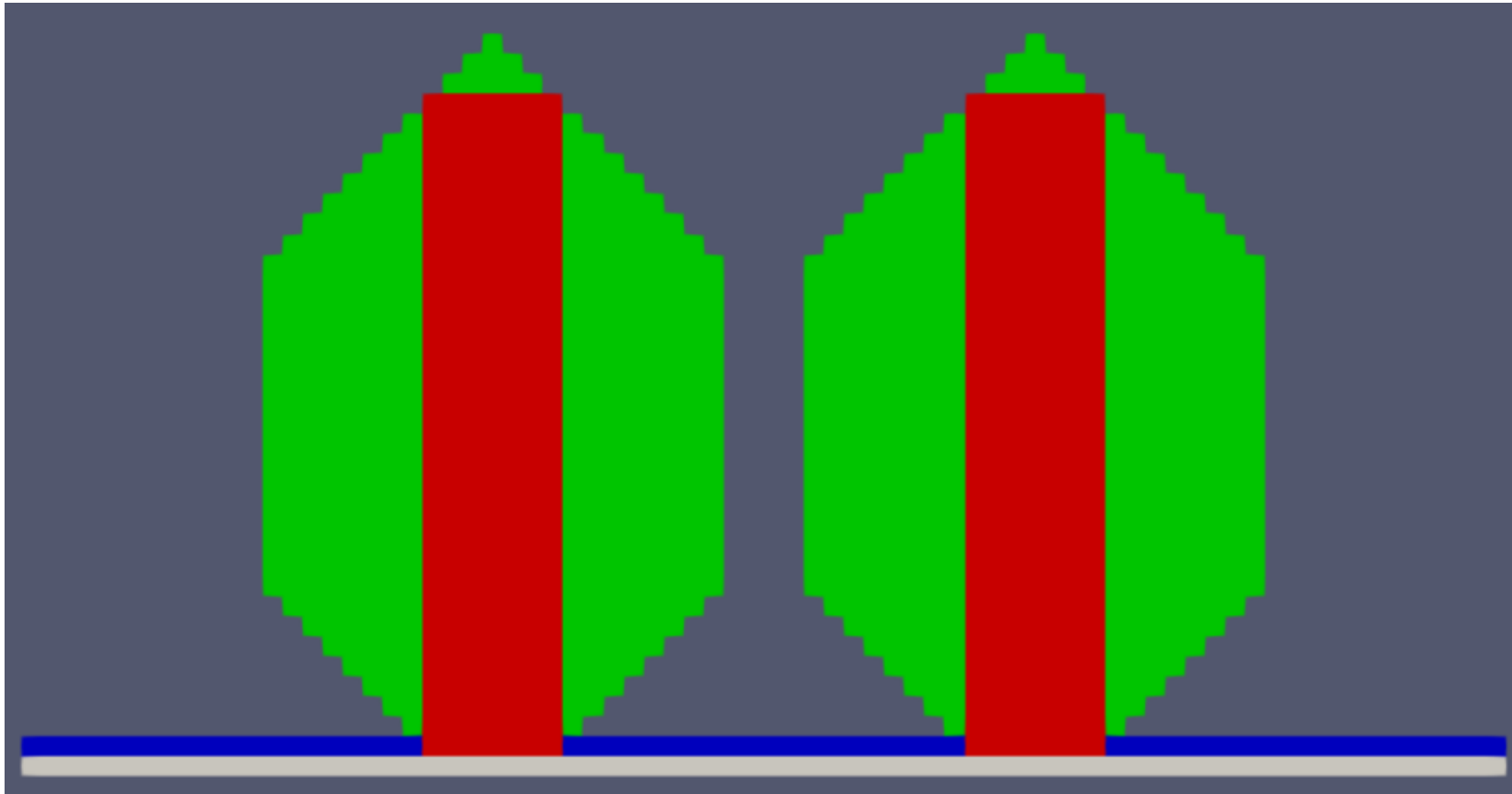
- This new statement takes three spec arguments.
 - Name of the added region: `region`
 - Name of the material selectivity: `model`
 - (Minimum) number of voxels to be added: `number`

`growth (region="SD",model="model_sd",number=12000)`

- DO NOT increase `number` too aggressively.
- Main idea
 - Check the existing surfaces.
 - {111} surfaces are approximated as diagonal surfaces. (45°)

When the number of voxels is 12000,

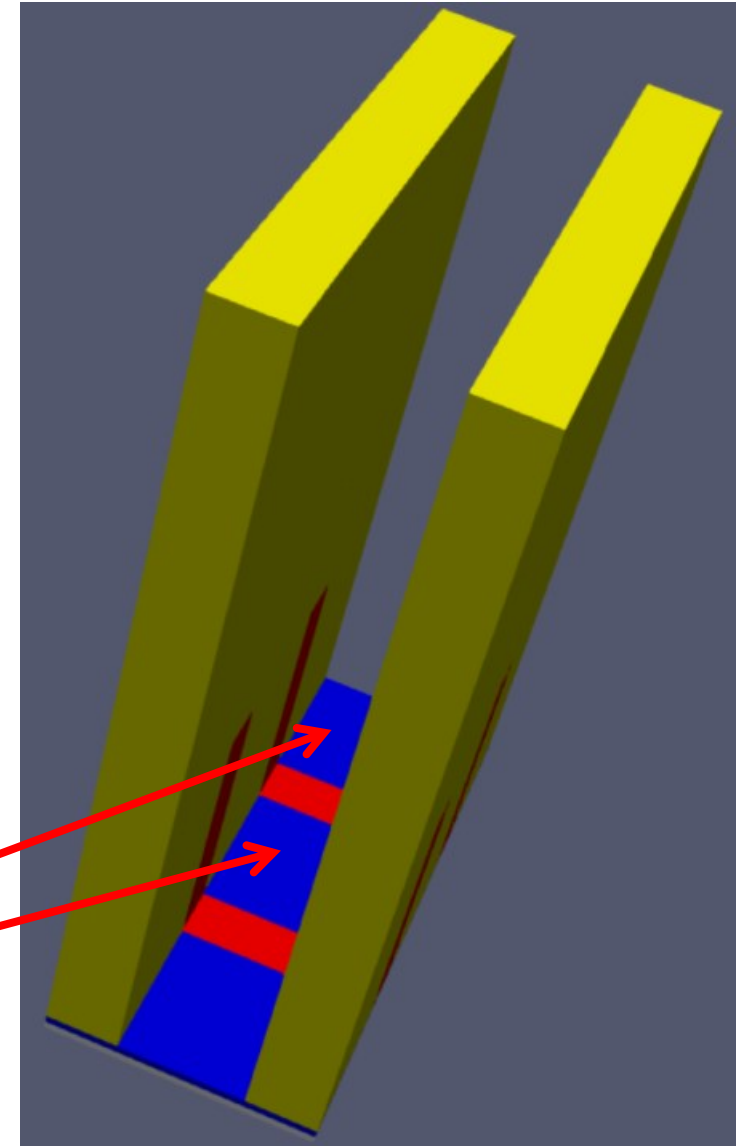
- We have a similar profile.
 - Of course, details cannot be reproduced.



Three-dimensional shape

- Cavity etching
 - The 32-nm-tall fin is etched anisotropically.
 - The fin underneath the spacer is not etched. → In reality, these parts are also etched.
 - Etch depth is equal to the fin height. → In reality, it is not.

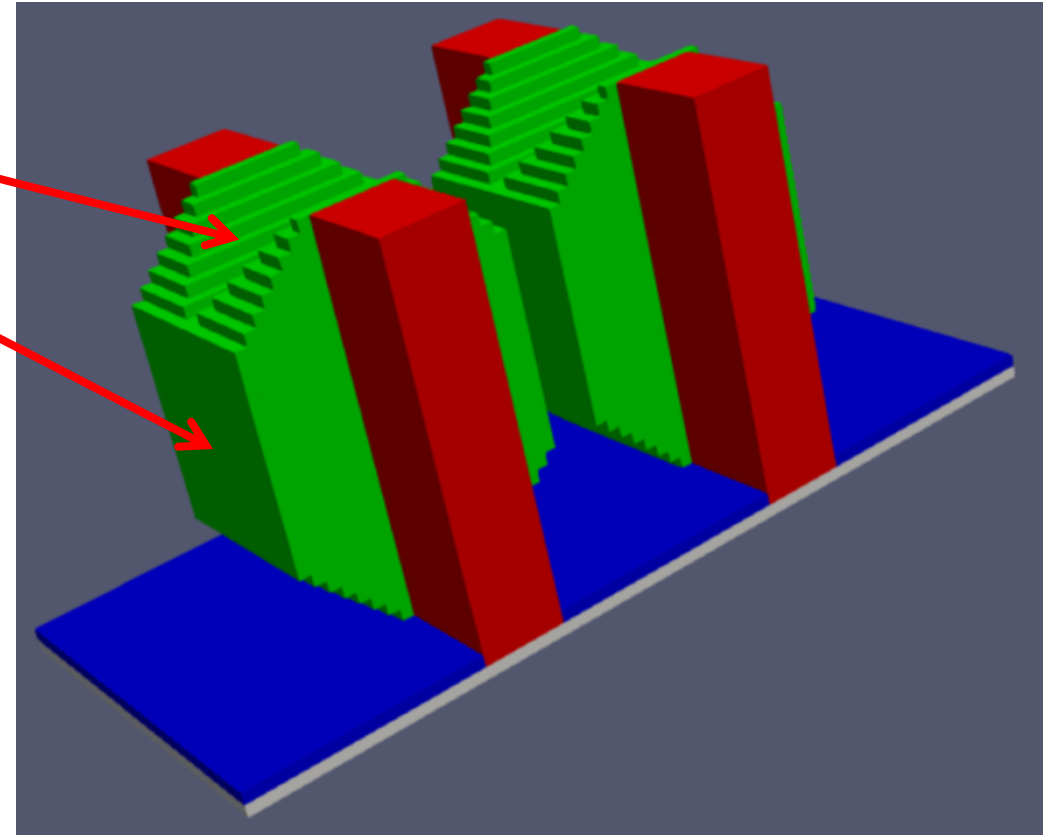
There is no fin.



Growth after cavity etching

- Contribution from two channels is dominant.
 - In this example, increased `number` introduces more voxels to make a diamond-like shape.

```
model (name="model_sd") {  
  select (region="Fin")  
  select (region="SD")  
  neighbor (region="Spacer")  
}
```



Homework#13

- Due: 08:00 on Nov. 3
- Submit a report through the GIST LMS system.
 - Construct the simple structure used in the L13 lecture material. Then, by using a `growth` statement, grow the epitaxial layer.

Thank you!